	Application No.	Applicant(s)
Notice of Allowability	10/686,769	SHONG ET AL.
	Examiner	Art Unit
	David Nhu	2818
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to <u>10/17/03</u> .		
2. The allowed claim(s) is/are <u>1-5.</u>		
3. The drawings filed on 17 October 2003 are accepted by the Examiner.		
4.		
Attachment(s)  1. ☑ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary Paper No./Mail Dat 8), 7. ☐ Examiner's Amendr 8. ☑ Examiner's Stateme 9. ☐ Other	e

Application/Control-Number: 10/686,769 Page 2

Art Unit: 2818

## **REASONS FOR ALLOWANCE**

1. Claims 1-5 are allowed.

2. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claim 1: A metal wiring method for an undercut in a MEMS packaging process, the method comprising: disposing a MEMS element on a silicon substrate; welding a glass wafer to an upper portion of the silicon substrate having the MEMS element disposed thereon, the glass wafer having a hole formed therein for connecting a metal wiring; depositing a thin metal for the metal wiring in the hole; and ion-mealing the deposited

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the

issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons

for Allowance."

thin metal film.

## Conclusion

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: MacDonald et al (5,198,390): RIE Process for Fabricating Submicron Silicon Electromechanical Structures.

5. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (571)272-1787.

Art Unit: 2818

The fax phone number for the organization where this application or proceeding is assigned is (703)872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956

David Nhu

M

August 18, 2004

DAMIDNHU

Xxii Da